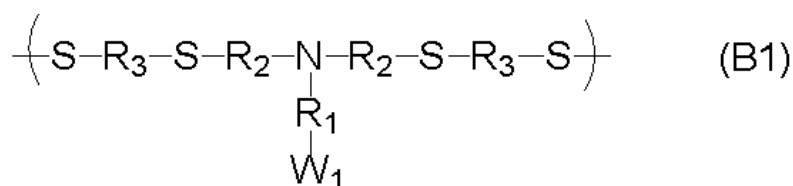


TITLE OF INVENTION: COMPOSITION FOR FORMING ORGANIC  
FILM, METHOD FOR FORMING ORGANIC FILM, PATTERNING  
PROCESS, AND POLYMER

ABSTRACT

The present invention is a polymer having a repeating unit represented by the following formula (B1).



In the formula,  $\text{R}_1$  represents a single bond or a divalent organic group having 1 to 6 carbon atoms,  $\text{R}_2$  represents a divalent organic group having 1 to 6 carbon atoms,  $\text{R}_3$  represents a divalent organic group having 1 to 30 carbon atoms and optionally having an oxygen atom, and  $\text{W}_1$  represents a fluorine-containing group. The polymer can provide a composition for forming an organic film that has excellent film formability (in-plane uniformity) on a substrate (a wafer) and filling properties and excellent hump-reducing properties in an EBR process, and that can form an organic film having excellent process margin when used as an organic film for a multilayer resist.

[FIG. 1(A)-1(F)]